Geok Ing Ng

List of Publications by Year in Descending Order

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2,765 26 41 207 h-index g-index citations papers 4.84 240 3,237 2.7 L-index avg, IF ext. citations ext. papers

#	Paper	IF	Citations
207	AlN/GaN MISHEMTs on Si with in-situ SiN as a gate dielectric for power amplifiers in mobile SoCs. <i>Applied Physics Express</i> , 2022 , 15, 016503	2.4	4
206	100 nm T-gate GaN-on-Si HEMTs Fabricated with CMOS-Compatible Metallization for Microwave and mm-Wave Applications 2021 ,		2
205	Phase noise reduction of a 2	8.6	3
204	GaN-on-Si HEMTs Fabricated With Si CMOS-Compatible Metallization for Power Amplifiers in Low-Power Mobile SoCs. <i>IEEE Microwave and Wireless Components Letters</i> , 2021 , 31, 141-144	2.6	4
203	Demonstration of vertically-ordered h-BN/AlGaN/GaN metal-insulator-semiconductor high-electron-mobility transistors on Si substrate. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , 2021 , 270, 115224	3.1	1
202	Enhancing the piezoelectric modulus of wurtzite AlN by ion beam strain engineering. <i>Applied Physics Letters</i> , 2021 , 118, 012108	3.4	4
201	On the recovery of 2DEG properties in vertically ordered h-BN deposited AlGaN/GaN heterostructures on Si substrate. <i>Applied Physics Express</i> , 2020 , 13, 065508	2.4	4
200	High-Frequency Characteristics of InGaP/GaAs Double Heterojunction Bipolar Transistor Epitaxially Grown on 200 mm Ge/Si Wafers. <i>IEEE Journal of the Electron Devices Society</i> , 2020 , 8, 122-125	2.3	0
199	Low Static and Dynamic On-Resistance with High Figure of Merit in AlGaN/GaN High Electron Mobility Transistors on Chemical Vapor Deposited Diamond. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2020 , 217, 1900815	1.6	1
198	Vertical GaN-on-GaN Schottky Diodes as ⊕article Radiation Sensors. <i>Micromachines</i> , 2020 , 11,	3.3	4
197	Change of high-voltage conduction mechanism in vertical GaNBntaaN Schottky diodes at elevated temperatures. <i>Applied Physics Express</i> , 2020 , 13, 074001	2.4	2
196	CMOS-compatible GaN-on-Si HEMTs with cut-off frequency of 210 GHz and high Johnson figure-of-merit of 8.8 THz V. <i>Applied Physics Express</i> , 2020 , 13, 026503	2.4	11
195	Improved breakdown voltage in vertical GaN Schottky barrier diodes on free-standing GaN with Mg-compensated drift layer. <i>Japanese Journal of Applied Physics</i> , 2020 , 59, 010906	1.4	4
194	Demonstration of AlGaN/GaN MISHEMT on Si with Low-Temperature Epitaxy Grown AlN Dielectric Gate. <i>Electronics (Switzerland)</i> , 2020 , 9, 1858	2.6	2
193	Investigations of temperature-dependent interface traps in AlGaN/GaN HEMT on CVD-diamond. <i>Applied Physics Express</i> , 2019 , 12, 106506	2.4	4
192	GaN drift-layer thickness effects in vertical Schottky barrier diodes on free-standing HVPE GaN substrates. <i>AIP Advances</i> , 2019 , 9, 045007	1.5	8
191	High temperature characteristics of a 2 th InGaSb/AlGaAsSb passively mode-locked quantum well laser. <i>Applied Physics Letters</i> , 2019 , 114, 221104	3.4	5

(2016-2019)

190	Deeply-scaled GaN-on-Si high electron mobility transistors with record cut-off frequency f T of 310 GHz. <i>Applied Physics Express</i> , 2019 , 12, 126506	2.4	14
189	Investigation of Self-Heating Effect on DC and RF Performances in AlGaN/GaN HEMTs on CVD-Diamond. <i>IEEE Journal of the Electron Devices Society</i> , 2019 , 7, 1264-1269	2.3	7
188	Low Voltage High-Energy Particle Detectors by GaN-on-GaN Schottky Diodes with Record-High Charge Collection Efficiency. <i>Sensors</i> , 2019 , 19,	3.8	6
187	InAlN/GaN HEMTs on Si With High \${{f}}_{text {T}}\$ of 250 GHz. <i>IEEE Electron Device Letters</i> , 2018 , 39, 75-78	4.4	36
186	Mid-Infrared Sensor Based on a Suspended Microracetrack Resonator With Lateral Subwavelength-Grating Metamaterial Cladding. <i>IEEE Photonics Journal</i> , 2018 , 10, 1-8	1.8	8
185	Planar Nanostrip-Channel Al2O3/InAlN/GaN MISHEMTs on Si With Improved Linearity. <i>IEEE Electron Device Letters</i> , 2018 , 39, 947-950	4.4	20
184	Investigation of regime switching from mode locking to Q-switching in a 2 \(\bar{\pm} \) m InGaSb/AlGaAsSb quantum well laser. <i>Optics Express</i> , 2018 , 26, 8289-8295	3.3	7
183	Experimental Demonstration of Thermally Tunable Fano and EIT Resonances in Coupled Resonant System on SOI Platform. <i>IEEE Photonics Journal</i> , 2018 , 10, 1-8	1.8	4
182	Planar-Nanostrip-Channel InAlN/GaN HEMTs on Si With Improved $q_{g}_{m}\$ and $f_{g}_{m}\$ and $f_{g}_{m}\$ Linearity. <i>IEEE Electron Device Letters</i> , 2017 , 38, 619-622	4.4	22
181	Investigation of gate leakage current mechanism in AlGaN/GaN high-electron-mobility transistors with sputtered TiN. <i>Journal of Applied Physics</i> , 2017 , 121, 044504	2.5	16
180	Conversion between EIT and Fano spectra in a microring-Bragg grating coupled-resonator system. <i>Applied Physics Letters</i> , 2017 , 111, 081105	3.4	16
179	Improved planar device isolation in AlGaN/GaN HEMTs on Si by ultra-heavy 131Xe+ implantation. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2017 , 214, 1600794	1.6	3
178	Flexible Ionic-Electronic Hybrid Oxide Synaptic TFTs with Programmable Dynamic Plasticity for Brain-Inspired Neuromorphic Computing. <i>Small</i> , 2017 , 13, 1701193	11	110
177	AlGaN/GaN high electron mobility transistors on Si with sputtered TiN gate. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2017 , 214, 1600555	1.6	8
176	Modal gain characteristics of a 2 th InGaSb/AlGaAsSb passively mode-locked quantum well laser. Applied Physics Letters, 2017 , 111, 251105	3.4	14
175	Dual-band optical filter based on a single microring resonator embedded with nanoholes 2017,		2
174	Compact microring resonators integrated with grating couplers working at 2 th wavelength on silicon-on-insulator platform. <i>Applied Optics</i> , 2017 , 56, 5444-5449	0.2	5
173	Low-Temperature Chemical Transformations for High-Performance Solution-Processed Oxide Transistors. <i>Chemistry of Materials</i> , 2016 , 28, 8305-8313	9.6	51

172	Electromagnetically induced transparency-like effect in microring-Bragg gratings based coupling resonant system. <i>Optics Express</i> , 2016 , 24, 25665-25675	3.3	16
171	(Invited) Novel Integrated Circuit Platforms Employing Monolithic Silicon CMOS + GaN Devices. <i>ECS Transactions</i> , 2016 , 75, 31-37	1	5
170	Thermally stable device isolation by inert gas heavy ion implantation in AlGaN/GaN HEMTs on Si. <i>Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics</i> , 2016 , 34, 042203	1.3	15
169	A Comprehensive Compact Model for GaN HEMTs, Including Quasi-Steady-State and Transient Trap-Charge Effects. <i>IEEE Transactions on Electron Devices</i> , 2016 , 63, 1478-1485	2.9	16
168	Temperature Dependent Characteristics of InAlN/GaN HEMTs for mm-Wave Applications. <i>Procedia Engineering</i> , 2016 , 141, 103-107		5
167	Role of two-dimensional electron gas (2DEG) in AlGaN/GaN high electron mobility transistor (HEMT) ON-state degradation. <i>Microelectronics Reliability</i> , 2016 , 64, 589-593	1.2	14
166	(Invited) SiGe and III-V Materials and Devices: New HEMT and LED Elements in 0.18-Micron CMOS Process and Design. <i>ECS Transactions</i> , 2016 , 75, 439-446	1	12
165	Low k-dielectric benzocyclobutane encapsulated AlGaN/GaN HEMTs with Improved off-state breakdown voltage. <i>Japanese Journal of Applied Physics</i> , 2015 , 54, 036504	1.4	5
164	Effect of OFF-state stress induced electric field on trapping in AlGaN/GaN high electron mobility transistors on Si (111). <i>Applied Physics Letters</i> , 2015 , 106, 083508	3.4	12
163	Electron velocity of 6 🛘 07 cm/s at 300 K in stress engineered InAlN/GaN nano-channel high-electron-mobility transistors. <i>Applied Physics Letters</i> , 2015 , 106, 053502	3.4	13
162	Conduction mechanism of non-gold Ta/Si/Ti/Al/Ni/Ta ohmic contacts in AlGaN/GaN high-electron-mobility transistors. <i>Applied Physics Express</i> , 2015 , 8, 041001	2.4	12
161	Impact of post-deposition annealing on interfacial chemical bonding states between AlGaN and ZrO2 grown by atomic layer deposition. <i>Applied Physics Letters</i> , 2015 , 106, 091603	3.4	10
160	Nano-channel InAlN/GaN Fin-HEMTs for ultra-high-speed electronics 2015,		3
159	Record-low contact resistance for InAlN/AlN/GaN high electron mobility transistors on Si with non-gold metal. <i>Japanese Journal of Applied Physics</i> , 2015 , 54, 04DF12	1.4	15
158	Effect of surface pretreatment on interfacial chemical bonding states of atomic layer deposited ZrO2 on AlGaN. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015 , 33, 05E1	177	1
157	Distribution of trap energy level in AlGaN/GaN high-electron-mobility transistors on Si under ON-state stress. <i>Applied Physics Express</i> , 2015 , 8, 104101	2.4	8
156	A silicon-nanowire memory driven by optical gradient force induced bistability. <i>Applied Physics Letters</i> , 2015 , 107, 261111	3.4	9
155	Study on GaN buffer leakage current in AlGaN/GaN high electron mobility transistor structures grown by ammonia-molecular beam epitaxy on 100-mm Si(111). <i>Journal of Applied Physics</i> , 2015 , 117, 245305	2.5	4

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154	Growth and characterization of AlGaN/GaN/AlGaN double-heterojunction high-electron-mobility transistors on 100-mm Si(111) using ammonia-molecular beam epitaxy. <i>Journal of Applied Physics</i> , 2015 , 117, 025301	2.5	11
153	GaN HEMT compact model for circuit simulation 2015,		1
152	Active current modeling for GaN HEMT devices. <i>Microwave and Optical Technology Letters</i> , 2015 , 57, 694-697	1.2	3
151	High Johnsonର figure of merit (8.32 THzѾ) in 0.15-μm conventional T-gate AlGaN/GaN HEMTs on silicon. <i>Applied Physics Express</i> , 2014 , 7, 044102	2.4	16
150	Improved device isolation in AlGaN/GaN HEMTs on Si by heavy Kr+ Ion implantation 2014,		3
149	A Compact Model for Generic MIS-HEMTs Based on the Unified 2DEG Density Expression. <i>IEEE Transactions on Electron Devices</i> , 2014 , 61, 314-323	2.9	21
148	Relative Intensity Noise of Silicon Hybrid Laser. <i>IEEE Journal of Quantum Electronics</i> , 2014 , 50, 466-473	2	2
147	. IEEE Electron Device Letters, 2014 , 35, 992-994	4.4	22
146	In0.17Al0.83N/AlN/GaN Triple T-shape Fin-HEMTs with gm=646 mS/mm, ION=1.03 A/mm, IOFF=1.13 µA/mm, SS=82 mV/dec and DIBL=28 mV/V at VD=0.5 V 2014 ,		3
145	Influence of post-deposition annealing on interfacial properties between GaN and ZrO2 grown by atomic layer deposition. <i>Applied Physics Letters</i> , 2014 , 105, 152104	3.4	12
144	Design of Coupled Three-Line Impedance Transformers. <i>IEEE Microwave and Wireless Components Letters</i> , 2014 , 24, 84-86	2.6	18
143	Zero voltage switching high efficiency power amplifier with parallel coupled line load. <i>Microwave and Optical Technology Letters</i> , 2014 , 56, 2926-2929	1.2	1
142	Band alignment between GaN and ZrO2 formed by atomic layer deposition. <i>Applied Physics Letters</i> , 2014 , 105, 022106	3.4	26
141	Improved microwave noise performance in 0.15 m AlGaN/AlN/GaN HEMTs on Silicon 2014 ,		1
140	Enhanced Breakdown Voltage With High Johnson's Figure-of-Merit in 0.3-\$mu{rm m}\$ T-gate AlGaN/GaN HEMTs on Silicon by \$({rm NH}_{4})_{2}{rm S}_{x}\$ Treatment. <i>IEEE Electron Device Letters</i> , 2013 , 34, 1364-1366	4.4	42
139	Demonstration of Submicron-Gate AlGaN/GaN High-Electron-Mobility Transistors on Silicon with Complementary Metal®xideBemiconductor-Compatible Non-Gold Metal Stack. <i>Applied Physics Express</i> , 2013 , 6, 016501	2.4	39
138	Random-telegraph-signal noise in AlGaN/GaN MIS-HEMT on silicon. <i>Electronics Letters</i> , 2013 , 49, 156-15	71.1	3
137	Atomic layer deposition of ZrO2 as gate dielectrics for AlGaN/GaN metal-insulator-semiconductor high electron mobility transistors on silicon. <i>Applied Physics Letters</i> , 2013 , 103, 142109	3.4	54

136	High-performance modulation-doped AlGaAs/InGaAs thermopiles for uncooled infrared FPA application. <i>Infrared Physics and Technology</i> , 2013 , 59, 182-187	2.7	1
135	Low-Contact-Resistance Non-Gold Ta/Si/Ti/Al/Ni/Ta Ohmic Contacts on Undoped AlGaN/GaN High-Electron-Mobility Transistors Grown on Silicon. <i>Applied Physics Express</i> , 2013 , 6, 116501	2.4	19
134	High performance modulation doped AlGaAs/InGaAs thermopiles (H-PILEs) for uncooled IR FPA utilizing integrated HEMT-MEMS technology 2013 ,		1
133	A nanoelectromechanical systems actuator driven and controlled by Q-factor attenuation of ring resonator. <i>Applied Physics Letters</i> , 2013 , 103, 181105	3.4	19
132	AlGaN/GaN MISHEMTs on silicon using atomic layer deposited ZrO2 as gate dielectrics 2013,		1
131	Reduction of current collapse in AlGaN/GaN MISHEMT with bilayer SiN/Al2O3 dielectric gate stack. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2013 , 10, 1421-1425		17
130	2013,		2
129	Demonstration of AlGaN/GaN High-Electron-Mobility Transistors on 100-mm-Diameter Si(111) by Ammonia Molecular Beam Epitaxy. <i>Applied Physics Express</i> , 2012 , 5, 091003	2.4	15
128	GaN-on-Silicon integration technology 2012 ,		3
127	Direct Current and Microwave Characteristics of Sub-micron AlGaN/GaN High-Electron-Mobility Transistors on 8-Inch Si(111) Substrate. <i>Japanese Journal of Applied Physics</i> , 2012 , 51, 111001	1.4	25
126	High-Responsivity Modulation-Doped AlGaAs/InGaAs Thermopiles for Uncooled IR-FPA Utilizing Integrated HEMTMEMS Technology. <i>IEEE Electron Device Letters</i> , 2012 , 33, 1243-1245	4.4	2
125	A modular approach to design a full three-way 8 to 18 GHz MMIC active circulator. <i>Microwave and Optical Technology Letters</i> , 2012 , 54, 2858-2861	1.2	
124	Positive Bias-Induced \$V_{rm th}\$ Instability in Graphene Field Effect Transistors. <i>IEEE Electron Device Letters</i> , 2012 , 33, 339-341	4.4	11
123	Compact true time delay line with partially shielded coplanar waveguide transmission lines 2012,		1
122	AlGaN/GaN two-dimensional-electron gas heterostructures on 200 mm diameter Si(111). <i>Applied Physics Letters</i> , 2012 , 101, 082110	3.4	85
121	Effective suppression of current collapse in both E- and D-mode AlGaN/GaN HEMTs on Si by [(NH4)2Sx] passivation 2012 ,		3
120	Direct Current and Microwave Characteristics of Sub-micron AlGaN/GaN High-Electron-Mobility Transistors on 8-Inch Si(111) Substrate. <i>Japanese Journal of Applied Physics</i> , 2012 , 51, 111001	1.4	36
119	High-Performance Modulation-Doped Heterostructure-Thermopiles for Uncooled Infrared Image-Sensor Application. <i>IEICE Transactions on Electronics</i> , 2012 , E95.C, 1354-1362	0.4	1

Integration of RF MEMS switches with pHEMT MMICs on GaAs 2011, 118 2 Temperature-dependent forward gate current transport in atomic-layer-deposited Al2O3/AlGaN/GaN metal-insulator-semiconductor high electron mobility transistor. Applied Physics 117 3.4 49 Letters, 2011, 98, 163501 Reduced surface leakage current and trapping effects in AlGaN/GaN high electron mobility 116 81 3.4 transistors on silicon with SiN/Al2O3 passivation. Applied Physics Letters, 2011, 98, 113506 Side-gate effects on the direct current and radio frequency characteristics of AlGaN/GaN 115 3.4 high-electron-mobility transistor on Si. Applied Physics Letters, 2011, 99, 163505 Temperature-Dependent Microwave Noise Characteristics in ALD \$hbox{Al}_{2}hbox{O}_{3}\$/AlGaN/GaN MISHEMTs on Silicon Substrate. IEEE Electron Device Letters, 6 114 4.4 2011, 32, 318-320 Comprehensive Study on the Bias-Dependent Equivalent-Circuit Elements Affected by PECVD SiN 6 113 2.9 Passivation in AlGaN/GaN HEMTs. IEEE Transactions on Electron Devices, 2011, 58, 473-479 High vertical breakdown strength in with low specific on-resistance AlGaN/AlN/GaN HEMTs on 112 2.5 9 silicon. *Physica Status Solidi - Rapid Research Letters*, **2011**, 5, 37-39 Improved Device Performance by Post-Oxide Annealing in Atomic-Layer-Deposited Al\$ {2}\$O\$ {3}\$/AlGaN/GaN Metal[hsulatorBemiconductor High Electron Mobility Transistor on 16 111 2.4 Si. *Applied Physics Express*, **2011**, 4, 104102 Improved Power Device Figure-of-Merit (\$4.0times 10^{8}\$ V\$^{2}\$ \$Omega^{-1}\$ cm\$^{-2}\$) in AlGaN/GaN High-Electron-Mobility Transistors on High-Resistivity 4-in. Si. Applied Physics Express, 110 2.4 43 **2011**, 4, 084101 Structural and Electrical Characterization of Al[sub x]Ga[sub 1₦]N/GaN Interfaces for UV 109 Photodetectors. Electrochemical and Solid-State Letters, 2010, 13, H301 Low Specific On-Resistance AlGaN/AlN/GaN High Electron Mobility Transistors on High Resistivity 108 12 Silicon Substrate. Electrochemical and Solid-State Letters, 2010, 13, H169 Demonstration of AlGaN/GaN high-electron-mobility transistors on 100 mm diameter Si(111) by 107 3.4 plasma-assisted molecular beam epitaxy. Applied Physics Letters, 2010, 97, 232107 Improved Linearity for Low-Noise Applications in 0.25-\$ muhbox{m}\$ GaN MISHEMTs Using ALD 106 43 4.4 \$hbox{Al}_{2}hbox{O}_{3}\$ as Gate Dielectric. IEEE Electron Device Letters, 2010, 31, 803-805 High Microwave-Noise Performance of AlGaN/GaN MISHEMTs on Silicon With 105 44 4.4 \$hbox{Al}_{2}hbox{O}_{3}\$ Gate Insulator Grown by ALD. IEEE Electron Device Letters, 2010, 31, 96-98 Accurate large-signal FET model tailored for switching-mode power amplifier design. IEICE 104 0.5 Electronics Express, **2010**, 7, 1672-1678 Analytical Modeling of High-Frequency Noise Including Temperature Effects in GaN HEMTs on 103 2.9 14 High-Resistivity Si Substrates. IEEE Transactions on Electron Devices, 2010, 57, 1485-1491 Study on the Temperature Dependence of the Microwave-Noise Characteristics in AlGaN/GaN 102 2.9 3 HEMTs. IEEE Transactions on Electron Devices, 2010, 57, 2353-2357 Study of current collapse by quiescent-bias-stresses in rf-plasma assisted MBE grown AlGaN/GaN 101 high-electron-mobility transistors. Solid-State Electronics, 2010, 54, 1430-1433

100	Improved recess-ohmics in AlGaN/GaN high-electron-mobility transistors with AlN spacer layer on silicon substrate. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2010 , 7, 2412-2414		18	
99	Electrothermal large-signal model of IIIIV FETs accounting for frequency dispersion and charge conservation 2009 ,		6	
98	Temperature dependent microwave noise parameters and modeling of AlGaN/GaN HEMTs on Si substrate 2009 ,		9	
97	Analytical modeling of the temperature dependent microwave noise in AlGaN/GaN HEMTs 2009,		1	
96	Electrothermal Large-Signal Model of IIIIV FETs Including Frequency Dispersion and Charge Conservation. <i>IEEE Transactions on Microwave Theory and Techniques</i> , 2009 , 57, 3106-3117	4.1	32	
95	Temperature dependence of Ohmic contact characteristics in AlGaN/GaN high electron mobility transistors from B 0 to 200 °C. <i>Applied Physics Letters</i> , 2009 , 94, 142105	3.4	53	
94	Improved Microwave Noise Performance by SiN Passivation in AlGaN/GaN HEMTs on Si. <i>IEEE Microwave and Wireless Components Letters</i> , 2009 , 19, 383-385	2.6	12	
93	Mechanism of Increased High-Frequency Channel Noise With PECVD SiN Passivation in AlGaN/GaN HEMTs. <i>IEEE Electron Device Letters</i> , 2009 , 30, 1122-1124	4.4	6	
92	Improved two-dimensional electron gas transport characteristics in AlGaN/GaN metal-insulator-semiconductor high electron mobility transistor with atomic layer-deposited Al2O3 as gate insulator. <i>Applied Physics Letters</i> , 2009 , 95, 223501	3.4	85	
91	Influence of Ammonia in the Deposition Process of SiN on the Performance of SiN/AlGaN/GaN Metal I hsulator B emiconductor High-Electron-Mobility Transistors on 4-in. Si(111). <i>Applied Physics Express</i> , 2009 , 2, 031001	2.4	20	
90	Sheet carrier density enhancement by Si3N4 passivation on nonpolar a-plane (11200) sapphire grown AlGaNtGaN heterostructures. <i>Applied Physics Letters</i> , 2008 , 92, 092116	3.4	10	
89	Temperature dependent microwave performance of AlGaN/GaN high-electron-mobility transistors on high-resistivity silicon substrate. <i>Thin Solid Films</i> , 2007 , 515, 4517-4521	2.2	46	
88	Effect of gate-source and gate-drain Si3N4 passivation on current collapse in AlGaNtaN high-electron-mobility transistors on silicon. <i>Applied Physics Letters</i> , 2007 , 90, 173504	3.4	41	
87	High temperature power performance of AlGaNGaN high-electron-mobility transistors on high-resistivity silicon. <i>Applied Physics Letters</i> , 2007 , 91, 083516	3.4	24	
86	Enhancement of both direct-current and microwave characteristics of AlGaN©aN high-electron-mobility transistors by furnace annealing. <i>Applied Physics Letters</i> , 2006 , 88, 023502	3.4	12	
85	Microwave noise characteristics of AlGaN/GaN HEMTs on high-resistivity silicon substrate 2005,		1	
84	A novel technology to form self-aligned emitter ledge for heterojunction bipolar transistors. <i>IEEE Electron Device Letters</i> , 2003 , 24, 628-630	4.4	8	
83	A fast noise and Z-parameter transformations between common emitter and common base InP DHBT. <i>IEEE Transactions on Microwave Theory and Techniques</i> , 2002 , 50, 1109-1113	4.1		

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82	Scaling of microwave noise and small-signal parameters of InP/InGaAs DHBT with high DC current gain. <i>IEEE Transactions on Electron Devices</i> , 2002 , 49, 1308-1311	2.9	2
81	Microwave noise performance of metamorphic InP/In0.53Ga0.47As/InP DHBT on GaAs substrates. <i>Microwave and Optical Technology Letters</i> , 2002 , 33, 306-308	1.2	
80	DC Characterization of Metamorphic InP/InGaAs Heterojunction Bipolar Transistors at Elevated Temperature. <i>Japanese Journal of Applied Physics</i> , 2002 , 41, 1136-1138	1.4	2
79	Studies on the Degradation of InP/InGaAs/InP Double Heterojunction Bipolar Transistors Induced by Silicon Nitride Passivation. <i>Japanese Journal of Applied Physics</i> , 2002 , 41, 1059-1061	1.4	12
78	Through wafer via hole by reactive ion etching of GaAs 2002,		2
77	Characterization of linearly graded metamorphic InGaP buffer layers on GaAs using high-resolution X-ray diffraction. <i>Thin Solid Films</i> , 2001 , 391, 36-41	2.2	19
76	High-frequency performance of metamorphic InP/In0.53Ga0.47As/InP DHBT in common base configuration on GaAs substrates. <i>Materials Science in Semiconductor Processing</i> , 2001 , 4, 647-649	4.3	
75	. IEEE Transactions on Electron Devices, 2001 , 48, 1492-1497	2.9	16
74	. IEEE Transactions on Electron Devices, 2001 , 48, 2192-2197	2.9	12
73	Investigation of the degradation of InGaAs/InP double HBTs under reverse base-collector bias stress. <i>IEEE Transactions on Electron Devices</i> , 2001 , 48, 2647-2654	2.9	8
72	Metamorphic InP/InGaAs heterojunction bipolar transistors on GaAs substrate: DC and microwave performances. <i>IEEE Transactions on Electron Devices</i> , 2001 , 48, 2671-2676	2.9	9
71	Microwave noise and power performance of metamorphic InP heterojunction bipolar transistors. <i>IEEE Transactions on Microwave Theory and Techniques</i> , 2001 , 49, 2408-2412	4.1	2
70	Single-step fabrication of surface relief diffractive optical elements on hybrid sol-gel glass. <i>Optical Engineering</i> , 2001 , 40, 2017	1.1	4
69	Optimization of InxGa1\(\mathbb{A}\)As/InyAl1\(\mathbb{J}\)As high electron mobility transistor structures grown by solid-source molecular beam epitaxy. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2001, 19, 490		1
68	Metamorphic In0.52Al0.48As/In0.53Ga0.47As high electron mobility transistors on GaAs with InxGa1\(\text{IP} \) graded buffer. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2001, 19, 2119		8
67	Growth optimization of InGaP layers by solid source molecular beam epitaxy for the application of InGaP/In0.2Ga0.8As/GaAs high electron mobility transistor structures. <i>Journal of Crystal Growth</i> , 2000 , 216, 51-56	1.6	8
66	The influence of different isolation processes on the performance of AlGaAs/GaAs heterojunction bipolar transistors for power applications. <i>Solid-State Electronics</i> , 2000 , 44, 1989-1995	1.7	
65	Band gap narrowing effect in Be-doped AlxGa1NAs studied by photoluminescence spectroscopy. <i>Solid-State Electronics</i> , 2000 , 44, 37-40	1.7	6

64	Optimization of InxGa1½P/In0.2Ga0.8As/GaAs high electron mobility transistor structures grown by solid source molecular beam epitaxy. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , 2000 , 75, 110-114	3.1	1
63	High-rate electron cyclotron resonance etching of GaAs via holes. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , 2000 , 74, 282-285	3.1	3
62	Electron cyclotron resonance etching of GaAs vias for monolithic microwave integrated circuits. <i>Optical Materials</i> , 2000 , 14, 223-227	3.3	1
61	Avalanche multiplication in InP/InGaAs double heterojunction bipolar transistors with composite collectors. <i>IEEE Transactions on Electron Devices</i> , 2000 , 47, 1125-1133	2.9	17
60	Current transient in polyimide-passivated InP/InGaAs heterojunction bipolar transistors: systematic experiments and physical model. <i>IEEE Transactions on Electron Devices</i> , 2000 , 47, 2261-2269	2.9	10
59	Electrical and optical characterization of regrown PHEMT layer structures on etched GaAs surfaces. Journal of Materials Science: Materials in Electronics, 2000, 11, 379-382	2.1	1
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4	Hot-carrier induced degradation in InP/InGaAs/InP double heterojunction bipolar transistors		4	
3	MMIC-based W-band Dicke switched direct-detection receiver		4	
2			5	
1	A miniaturized W-band monolithic dual-gate InAlAs/InGaAs HEMT mixer		3	